

**AMENDMENTS TO THE CLAIMS**

1. **(Currently Amended)** A protective film for polarizing plate having a substrate film of a resin material and, laminated on at least one surface thereof directly or via another layer, a hard-coat layer and an antireflection layer that are laminated in this order, characterized in that the substrate film has a photoelastic coefficient of less than  $9 \times 10^{-12} \text{ Pa}^{-1}$  and a saturated water-absorbing percentage of less than 0.05%, and exhibits a warpage percentage of 1% or less when formed into a film having an average thickness of 50  $\mu\text{m}$  and a dimension of 100 mm x 100 mm and allowed to stand at 60°C and a humidity of 95% for 500 hours, and the antireflection layer includes a low refractive index layer and a high refractive index layer in this order from the hard-coat layer.

2. (Original) The protective film for polarizing plate according to claim 1, wherein the resin material contains an alicyclic structure-containing polymer.

3. **(Currently Amended)** The protective film for polarizing plate according to claim 1 or 2, wherein the antireflection layer is a ~~single layer or~~ multilayer film with two or more layers of an inorganic oxide.

4. (Previously Presented) A method for preparing the protective film for polarizing plate according to claim 1, comprising a step of forming an antireflection layer on the surface of a substrate film made of a resin material or on the surface of any layer formed on the substrate film, characterized in that the antireflection layer is formed by an ion-plating method, sputtering method, vacuum evaporation method, electroless plating method, electroplating method, or a combination of two or more of these methods.

5. (Original) The method for preparing the protective film for polarizing plate according to claim 4, wherein the step of forming an antireflection layer comprises sequentially laminating two or more thin layers of inorganic oxide on the surface of a substrate film or on the

surface of any layer formed on the substrate film, wherein the substrate film, with or without any other layer formed thereon, is preferably caused to pass through a series of film-forming chambers, each equipped with a means for forming a thin layer of inorganic oxide, whereby two or more thin layers of inorganic oxide are sequentially formed on the surface of the substrate film or on the surface of any layer formed on the substrate film.

6. (Previously Presented) The method for preparing the protective film for polarizing plate according to claim 4, wherein the substrate film is made from a resin material containing an alicyclic structure-containing polymer.

7. (Previously Presented) A polarizing plate with antireflection function comprising a polarizing plate laminated on one side of the substrate film of the protective film for polarizing plate according to claim 1 on which the antireflection layer is not provided.

8. (Original) An optical article equipped with the polarizing plate with antireflection function according to claim 7.

9. (New) The protective film for polarizing plate according to claim 1, wherein the substrate film has a volatile component content of 0.05 wt % or less.

10. (New) The protective film for polarizing plate according to claim 1, wherein the low refractive index layer is formed of  $\text{SiO}_2$ , the high refractive index layer is formed of ITO, and the hard-coat layer is formed of urethane acrylate.

11. (New) The method for preparing the protective film for polarizing plate according to claim 4, wherein the substrate film is obtained by melt extrusion molding using an extruder having a T-die, the melt extrusion molding including a step of delivering a molten resin material extruded from the extruder to a series of externally installed cooling drums comprising a first cooling drum, a second cooling drum, and a third cooling drum, in which the resin material is

cooled in this order, and the ratio of the circumferential speed  $R_3$  of the third cooling drum to the circumferential speed  $R_2$  of the second cooling drum ( $R_3/R_2$ ) is 0.99 - 1.00.

12. (New) The method for preparing the protective film for polarizing plate according to claim 11, wherein the ratio of the circumferential speed  $R_2$  of the second cooling drum to the circumferential speed  $R_1$  of the first cooling drum ( $R_2/R_1$ ) is less than 1.01 but 0.99 or more.

13. (New) The method for preparing the protective film for polarizing plate according to claim 11, wherein the temperature difference between the first cooling drum and the second cooling drum is 20°C or less.